

CLAIMS

What is claimed is:

1 1. A method for coating an uniform resist layer onto a plurality of non-planar sliders,
2 said method comprising:

3 spinning an elastic layer on a wafer;

4 curing said elastic layer;

5 spinning a resist layer on said elastic layer;

6 peeling said resist layer and said elastic layer together off from said wafer;

7 applying said peeled resist layer and elastic layer onto a plurality of
8 magnetic heads with said resist layer in direct contact with said plurality of
9 magnetic heads; and

10 peeling said elastic layer off from said resist layer such that said resist layer
11 remains attaching to said plurality of magnetic heads.

1 2. The method of Claim 1, wherein said elastic layer is poly-dimethyl siloxane.

1 3. The method of Claim 1, wherein said resist layer is a positive tone resist layer.

1 4. The method of Claim 1, wherein said wafer is a silicon wafer.

1 5. The method of Claim 1, wherein said curing further includes curing said elastic
2 layer at approximately 110 °C for about 8 minutes.

1 6. The method of Claim 1, wherein said applying further includes applying with a
2 roller.

1 7. The method of Claim 6, wherein said applying further includes applying with a
2 roller at approximately 25 °C and pressure at approximately 1 psi.

1 8. The method of Claim 1, wherein said method further includes baking said resist
2 layer at a temperature between approximately 70 °C to 80 °C after said resist layer has
3 been spun on said elastic layer.

9. A method for coating an uniform resist layer onto a plurality of non-planar sliders, said method comprising:

molding an elastic layer;

curing said elastic layer;

spinning a resist layer on said elastic layer;

applying said peeled resist layer and elastic layer onto a plurality of magnetic heads with said resist layer in direct contact with said plurality of magnetic heads; and

peeling said elastic layer off from said resist layer such that said resist layer remains attaching to said plurality of magnetic heads.

1 10. The method of Claim 9, wherein said elastic layer is poly-dimethyl siloxane.

1 11. The method of Claim 9, wherein said resist layer is a positive tone resist layer.

1 15. The method of Claim 9, wherein said curing further includes curing said elastic
2 layer at approximately 110 °C for about 8 minutes.

1 16. The method of Claim 9, wherein said applying further includes applying with a
2 roller.

1 17. The method of Claim 16, wherein said applying further includes applying with a
2 roller at approximately 25 °C and pressure at approximately 1 psi.

1 18. The method of Claim 9, wherein said method further includes baking said resist
2 layer at a temperature between approximately 70 °C to 80 °C after said resist layer has
3 been spun on said elastic layer.